## **AMENDMENTS TO THE CLAIMS**

This listing of claims will replace all prior versions and listings of claims in the application:

## **LISTING OF CLAIMS:**

Claim 1 (currently amended): A positive photoresist composition comprising:

- (A) an alkali-soluble resin;
- (B) a photosensitizer comprising a quinonediazide ester between a naphthoquinonediazidosulfonic acid compound and [[at least one of a compound represented by following Formula (I):

(I)

wherein R<sup>1</sup>, R<sup>2</sup>, R<sup>3</sup>, R<sup>4</sup>, R<sup>5</sup>, R<sup>6</sup>, R<sup>7</sup> and R<sup>8</sup> are each independently a hydrogen atom or an alkyl group having from 1 to 3 carbon atoms, and]] a compound represented by following Formula (II):

(II)

AMENDMENT UNDER 37 C.F.R. § 1.111

U.S. Application No.: 10/035,137 Attorney Docket No.: Q67940

wherein R<sup>9</sup>, R<sup>10</sup>, R<sup>11</sup>, R<sup>12</sup>, R<sup>13</sup>, R<sup>14</sup>, R<sup>15</sup>, R<sup>16</sup>, R<sup>16</sup>, R<sup>17</sup> and R<sup>18</sup> are each independently a hydrogen atom, an alkyl group having from 1 to 3 carbon atoms or a cyclohexyl group; and

(C) a sensitizer comprising at least one of compounds represented by following Formula (III):

(III)

wherein x is 0 or 1.

Claim 2 (cancelled).

Claim 3 (original): The positive photoresist composition according to claim 1, wherein the compound represented by Formula (II) is a compound represented by the following formula:

Claim 4 (original): The positive photoresist composition according to claim 1, wherein the compound represented by Formula (III) is a compound represented by the following formula:

Claim 5 (original): The positive photoresist composition according to claim 1, wherein the compound represented by Formula (III) is a compound represented by the following formula: